

# UNITED STATES DEPARTMENT OF COMMERCE Patent and Trademark Offic

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APPLICATION NO.	FILING DATE /	FIRST NAME	D INVENTOR		ATTORNEY DOCKET NO	<del>. ('</del> /'
09/405,210	09/24/99	MARCHANT		B	18865-3209	
020350		MMC2/1025	7	EXAMINER		
TOWNSEND AND TOWNSEND AND CREW TWO EMBARCADERO CENTER				VU.D ART UNIT	PAPER NUMBE	TN)
EIGHTH FLOOR SAN FRANCISCO	O CA 94111-:	3834		2818		4
				DATE MAILED		
					10/25/00	

Please find below and/or attached an Office communication concerning this application or proceeding.

**Commissioner of Patents and Trademarks** 

B				
	Application No.	Applicant(s)	Applicant(s)	
Office Action Summary	09/405,210	MARCHANT ET	MARCHANT ET AL.	
	Examiner	Art Unit		
	DAVID VU	2818		
The MAILING DATE of this communication appe Period for Reply	ars on the cover sheet with t	he correspondence ad	idress	
A SHORTENED STATUTORY PERIOD FOR REPLY THE MAILING DATE OF THIS COMMUNICATION.				
Extensions of time may be available under the provisions of 37 (after SIX (6) MONTHS from the mailing date of this communic.     If the period for reply specified above is less than thirty (30) days be considered timely.     If NO period for reply is specified above, the maximum statutory communication.     Failure to reply within the set or extended period for reply will, by Status	e, a reply within the statutory minim period will apply and will expire SI	um of thirty (30) days will K (6) MONTHS from the ma	ailing date of this	
1) Responsive to communication(s) filed on 24 Se				
0-1/3 =				
-5/E3 THIS	action is non-final.			
3) Since this application is in condition for allowant closed in accordance with the practice under E	ice except for formal matters x parte Quavie, 1935 C.D. 1	s, prosecution as to th	ne merits is	
Disposition of Claims	, , , , , , , , , , , , , , , , , , , ,	1, 400 O.G. 213.		
4) Claim(s) 1-17 is/are pending in the application.				
4a) Of the above claim(s) is/are withdraw 5) Claim(s) is/are allowed.	n from consideration.			
6)⊠ Claim(s) <u>1-17</u> is/are rejected.		,		
7) Claim(s) is/are objected to.				
8) Claims are subject to restriction and/or e	lection requirement.			
Application Papers				
9) The specification is objected to by the Examiner.				
10) The drawing(s) filed on is/are objected to t	by the Examiner.			
11) The proposed drawing correction filed oni	s: a)□ approved b)□ disa	approved.		
12) The oath or declaration is objected to by the Exar	miner.			
Priority under 35 U.S.C. § 119				
_			•	
13) Acknowledgment is made of a claim for foreign pr	ionty under 35 U.S.C. § 119 -	(a)-(d).	,	
a) ☐ All b) ☐ Some * c) ☐ None of the CERTIFIED	copies of the priority docur	ments have been:		
22 Production (40: (Genes Code)	Serial Number)			
3. received in this National Stage application for	rom the International Bureau	u (PCT Rule 17.2(a)).		
* See the attached detailed Office action for a list of the				
14) Acknowledgement is made of a claim for domestic	priority under 35 U.S.C. &	119(e).		
tachment(s)				
i) ⊠ Notice of References Cited (PTO-892) i) ☑ Notice of Draftsperson's Patent Drawing Review (PTO-948) i) ☑ Information Disclosure Statement(s) (PTO-1449) Paper No(s) 3.	18) Interview Summ 19) Notice of Inform 20) Other:	ary (PTO-413) Paper No(s al Patent Application (PTO	) -152)	

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#### **DETAILED ACTION**

### **Drawings**

The drawings are objected to under 37 CFR 1.83(a). The drawings must show every feature of the invention specified in the claims. Therefore, in claim 12, an angle resulting in a slanted edge along the etched side of the source region must be shown in Figs. 2A-2B and Fig. 4. No new matter should be entered.

#### Claim Rejections - 35 USC § 102

The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

1. Claims 1-17 are rejected under 35 U.S.C. 102(b) as being anticipated by Applicant's Application Background, pages 1-2 and Fig.1.

Applicant's Application Background, pages 1-2 and Fig.1, disclosees a process for manufacturing a trench field effect transistor comprising the steps of:

etching a first trench in a substrate having a first conductivity type;

lining the first trench with a layer of dielectric material;

substantially filling the trench with conductive material to form a gate electrode of the field effect transistor;

implanting impurities of a second conductivity type into the substrate to form a body region having the second conductivity type over the substrate; implanting impurities of the first conductivity type inside the body region to form a source region adjacent to the first trench;

etching a second trench through the source region and into the body region; and filling the second trench with conductive material for making contact with both the source region and the body region.

# Claim Rejections - 35 USC § 103

The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all obviousness rejections set forth in this Office action:

- (a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.
- 2. Claims 9,11,15,17 are rejected under 35 U.S.C. 103(a) as being unpatentable over Applicant's Application Background, pages 1-2 and Fig.1.

Applicant's Application Background, pages 1-2 and Fig.1, discloses all claimed subject matter, but omits the step of etching the second trench etches the second trench deeper than the first trench.

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However, the implanting energy, dosage, thickness, depth are considered to involve routine optimization which has been held to be within the level of ordinary skill in the art. As noted in In re Aller, the selection of reaction parameters such as energy, dosage, thickness, width and temperature, etc. would have been obvious: "Normally, it is to be expected that a change in energy, concentration, thickness, dosage, temperature, or combination of any of them would be an unpatentable modification. Under some circumstances, however, changes such as these may impart patentability to a process if the particular ranges claimed produce a new and unexpected result which is different in kind and not merely degree from the results of the prior art ... such ranges are termed "critical ranges and the applicant has the burden of proving such criticality.... More particularly, where the general conditions of a claim are disclosed in the prior art, it is not inventive to discover the optimum or workable ranges by routine experimentation." In re Aller 105 USPQ233, 255 (CCPA 1955). See also In re Waite 77 USPQ 586 (CCPA 1948); In re Scherl 70 USPQ 204 (CCPA 1946); In re Irmscher 66 USPQ 314 (CCPA 1945); In re Norman 66 VSPQ 3 08 (CCPA 1945); In re Swenson 56 USPQ 3 72 (CCPA 1942); In re Sola 25 USPQ 433 (CCPA 1935); In re Dreyfus 24 USPQ 52 (CCPA 1934). Therefore, one of ordinary skill in the requisite art at the time the invention was made would have used any energy, concentration, thickness, depth range suitable to the method in process of Applicant's Application Background, pages 1-2 and Fig.1, in order to improve the performance of the semiconductor device.

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## Conclusion

4. Any inquiry concerning this communication or earlier communications from the examiner should be directed to David Vu whose telephone number is (703) 305-0391. The examiner can normally be reached on Monday-Friday from 8:00am to 5:00pm. If attempt to reach the examiner by telephone are unsuccessful, the examiner's supervisor, David Nelms., can be reached on (703) 308-4910.

David Vu

DV

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Dávíð Nelms Supervisory Patent Examiner Technology Center 2800